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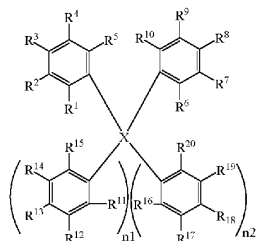
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(I)

(57) Abstract: Crosslinking aromatic compounds are described which have structure (I). Also described, are compositions including these crosslinking compounds, for instance ones which also comprising a photoacid generator. Also, described are methods of using such compositions to coat a substrate and by exposing it to radiation producing an image which may be used as a mask in the manufacture of microelectronics. Also disclosed is a selective iodination method for multiphenolic compounds at the ortho position to the phenol functionality, employing a 1-iodopyrrolidine-2,5-dione moiety in the presence of an arylsulfonic acid which produces the phenolic precursors of crosslinking aromatic compounds with selective iodination.

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